

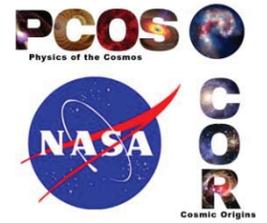
Recent Progress on 2012 SAT for UVOIR Coatings

2014 Mirror Technology/SBIR/STTR Workshop

By

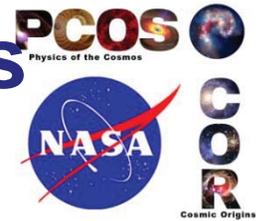
Manuel Quijada

Outline



- Motivation: The need for better performing coatings in the Far-Ultraviolet (FUV)
- Project Objectives
- Methods & Facilities
- Results
- Conclusions & Future Plans
- Acknowledgements

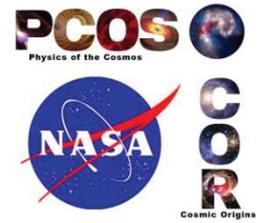
Enhanced FUV Coating Applications



- Distant and faint objects are typically searched for in cosmic origin studies:
 - Origin of large scale structure
 - The formation, evolution, and age of galaxies
 - The origin of stellar and planetary systems
- Astronomical observations in the Far Ultraviolet (FUV) spectral region are some of the more challenging
- Very limited option of reflecting coatings to use at FUV wavelengths:
 - Modest reflectivity offered by those coatings
 - Al+MgF₂ [typically 82% at Lyman-alpha, 1216 Å) that are used on reflecting surfaces of FUV instrumentation
- Improved reflective coatings for optics at FUV could yield dramatically more sensitive instruments .
- Permit more instrument design freedom

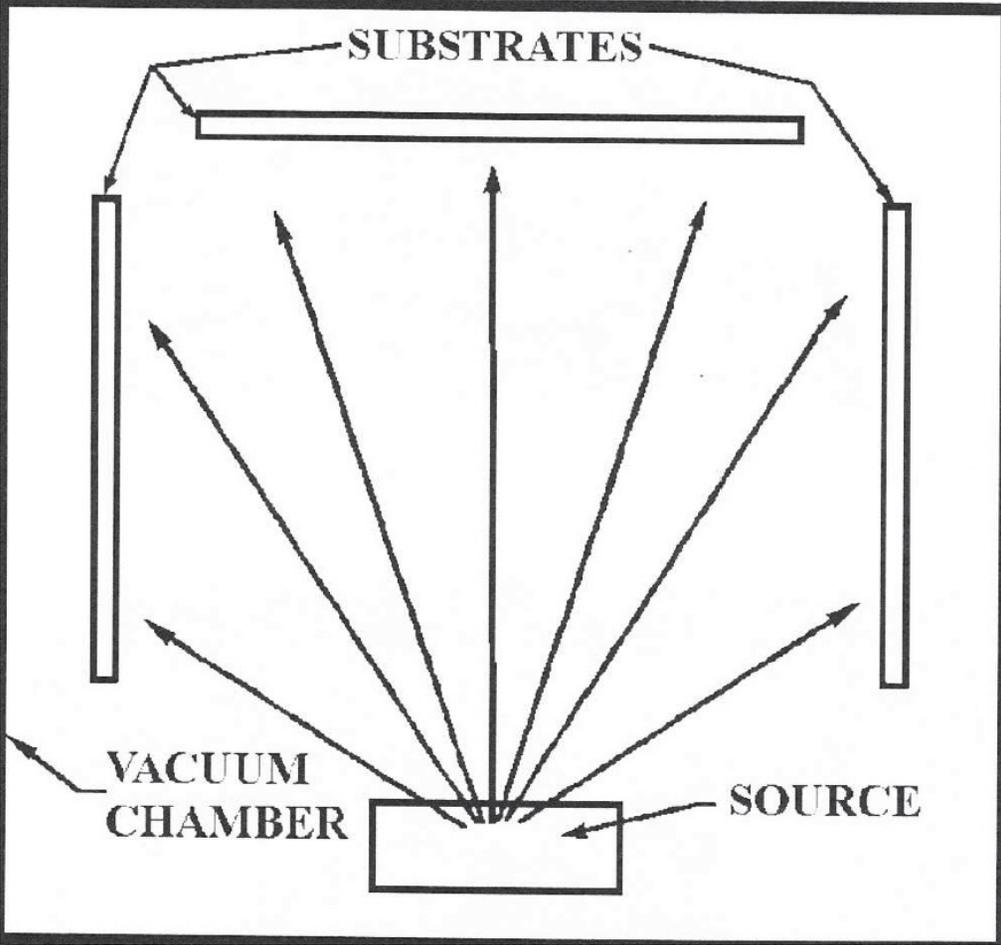


Project Objectives

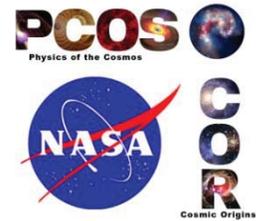


- Develop coating deposition processes to improve performance in Far Ultraviolet (FUV)
- Three main objectives:
 - Use a reactive Ion Beam Sputtering process to make better MgF_2 films
 - Study low-absorption materials for dielectric coatings in FUV spectral region
 - Improved FUV reflectance performance of aluminum mirrors over-coated with MgF_2 and LiF
- 3-year performance period (Started in FY12)

Physical Vapor Deposition



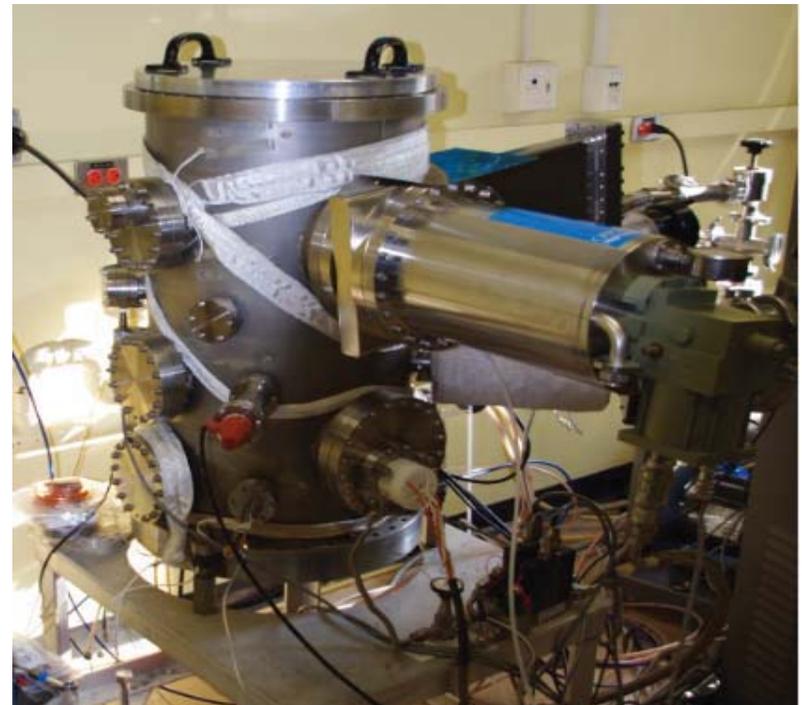
GSFC Coating Facilities



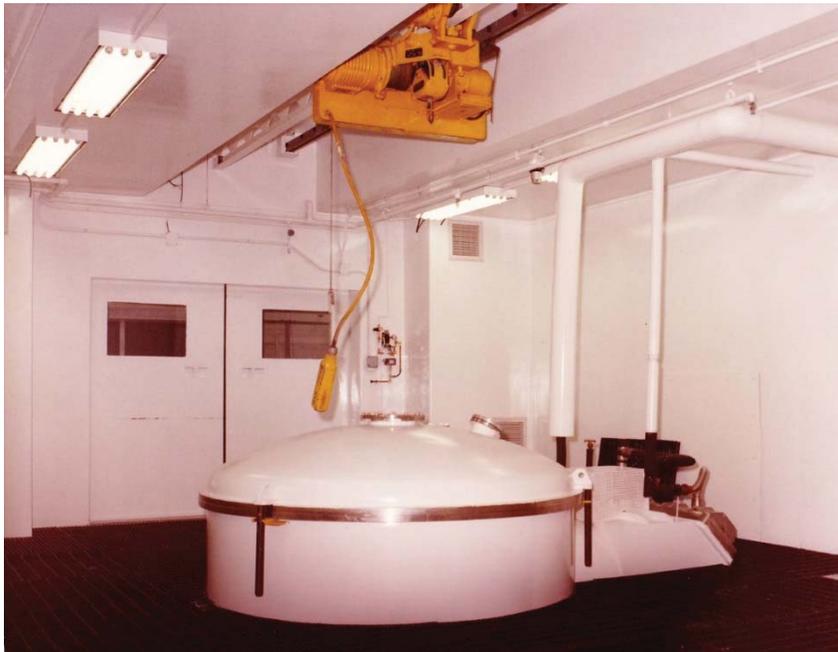
- PVD, IBS, and RF Magnetron Sputtering deposition chambers
- Coatings produced: Al, MgF₂, SiO_x, LiF, Al₂O₃, Ag, Cr, Y₂O₃



PVD coating chamber (1-meter)



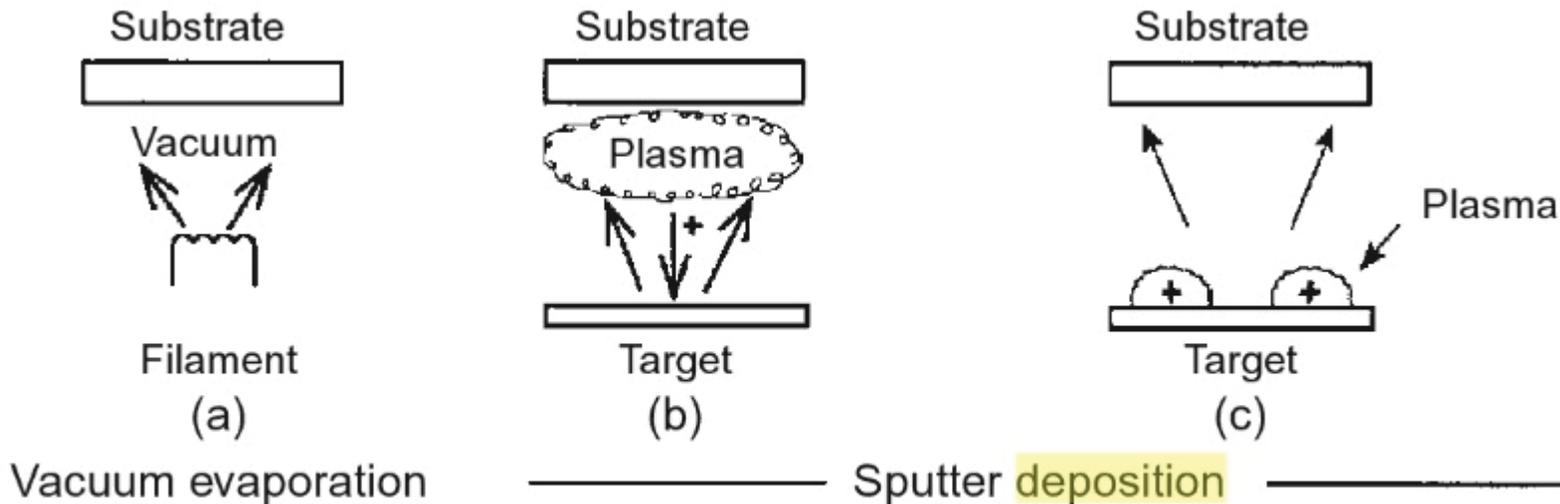
Reactive Ion Beam Sputtering



Chamber top Cover with mirror substrate installed

Missions supported: Astronomical Observatory (OAO) & Ultraviolet Explorer (IUE)
FUSE, HST (COSTAR, GHRS & COS)

Coating Deposition Processes



PVD

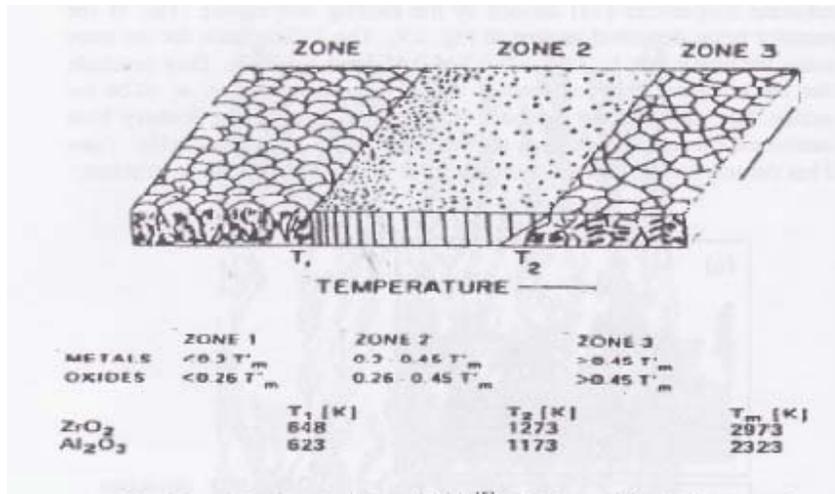
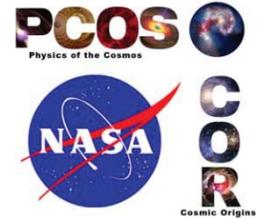
- Material is heated until it reaches vapor form
- Material is deposited on the substrate where it condenses
- Typical deposition rates are $10-100 \text{ \AA/Sec}$.

Sputtering

- Non-thermal evaporation process
- Atoms from a target are ejected by momentum transfer from energetic atom-size particles
- Particles are energized by an ion gun
- Deposition rates are much lower than PVD $1-5 \text{ \AA/Sec}$.



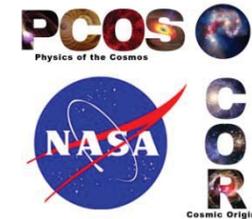
Model of Film Growth vs. Temperature



Computer simulation growth process (Karl Gunther)

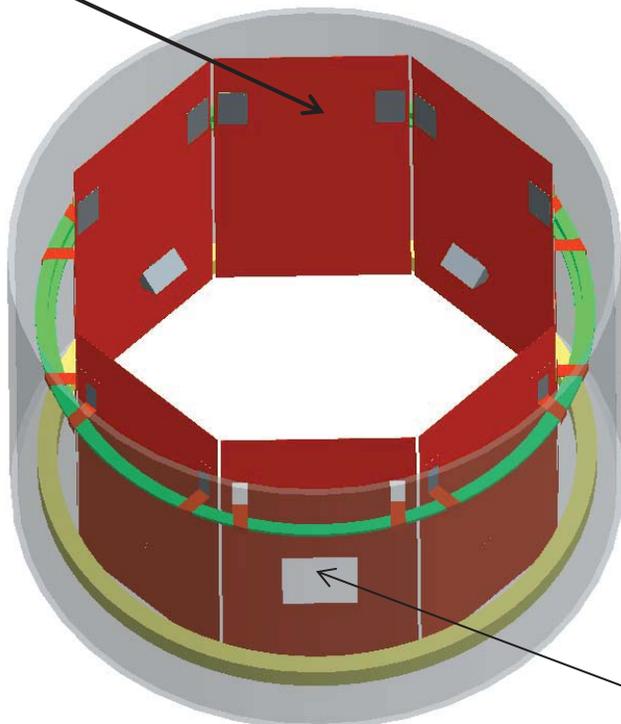
- Zone model of film growth vs. substrate temperature (After Movchan & Denchishin (1969))
- Three zones as function of T_s/T_m
 - Zone 1 (< 0.25): Feathery “frost” with columnar growth separated by many voids
 - Zone 2 (0.25 to 0.45): Densely packed columns
 - Zone 3 (> 0.45): Polycrystalline structure

2-meter Chamber Heat Panel Concept

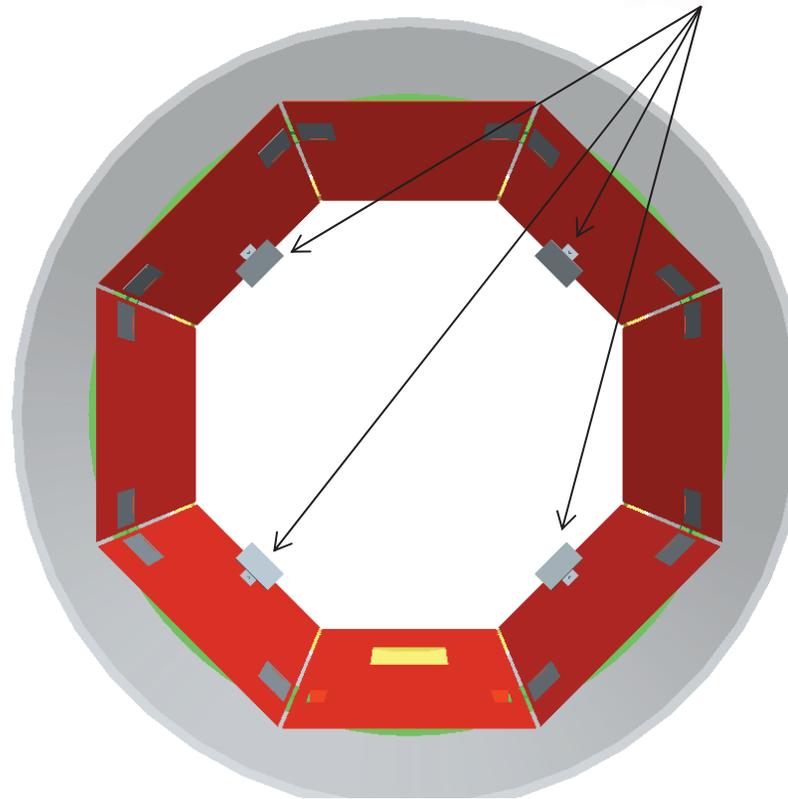


- Design and fabrication of internal heat shields for 2-meter Chamber.
- Optimized coating parameter for high FUV reflectance of a distribution of slides in center and out to a ~0.5 meter radius.
- These wall panels were made out of stainless steel and were designed to easily interface with the existing internal configuration of the chamber.

8 PANELS

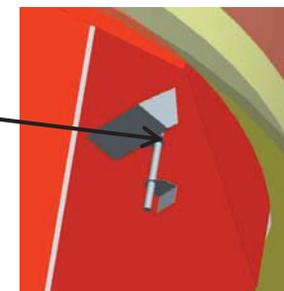


4X LIGHT MOUNTS



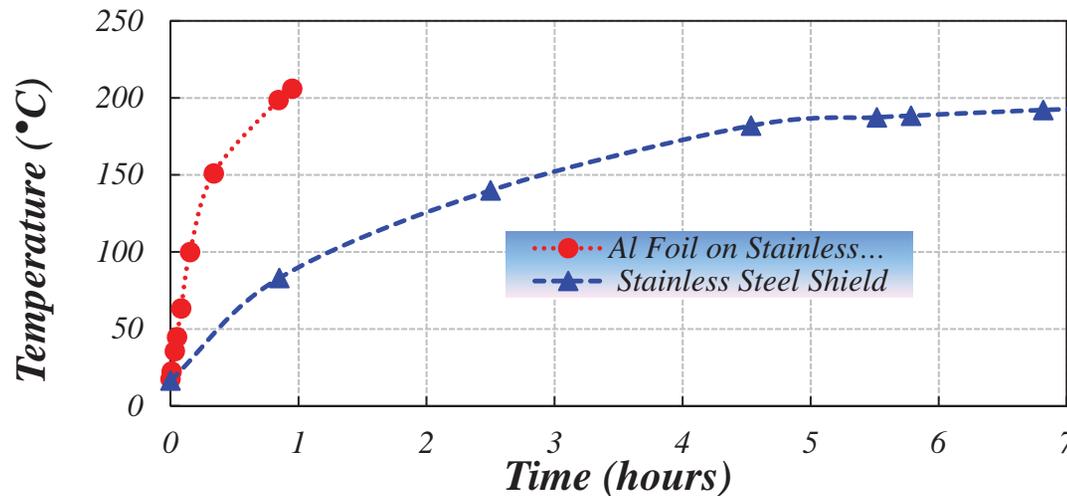
ADJUSTABLE LIGHT MOUNT

SINGLE VIEWPORT
10" X 10"
SQUARE

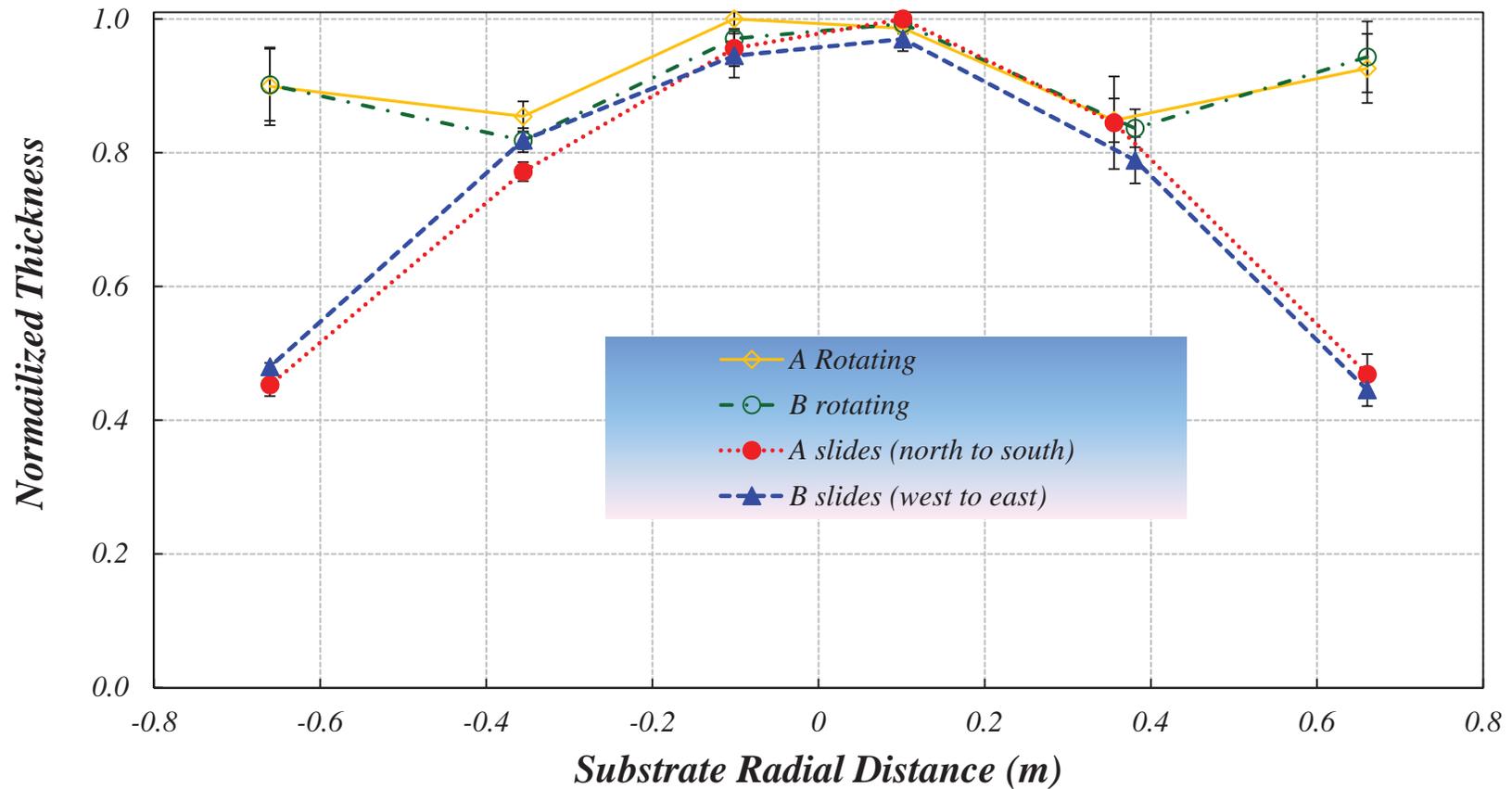


2-meter Chamber Heater Check Out Process

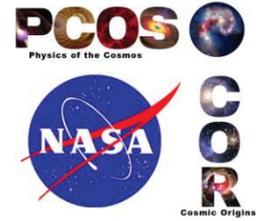
- Earlier test of heaters showed maximum temperature reached was only 100 ° C after 5 hours
- Doubled lamp power output from 500 W to 1000 W each (4000 W total)
- Additional testing yielded a maximum temperature of 130 ° C
- Further testing done after wrapping heat shield panels with **aluminum foil** provide for a much quicker raise in temperature, reaching 220 ° C in less than 1 hour



Thickness Uniformity



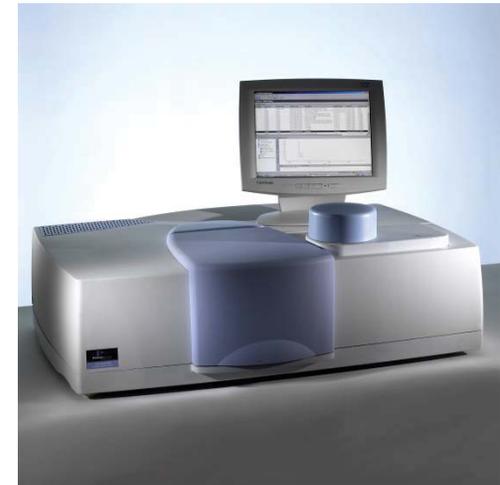
Optical Characterization: $T(\lambda)$, $R(\lambda)$



ACTON VUV Spectrometer



Perkin Elmer Lambda 950

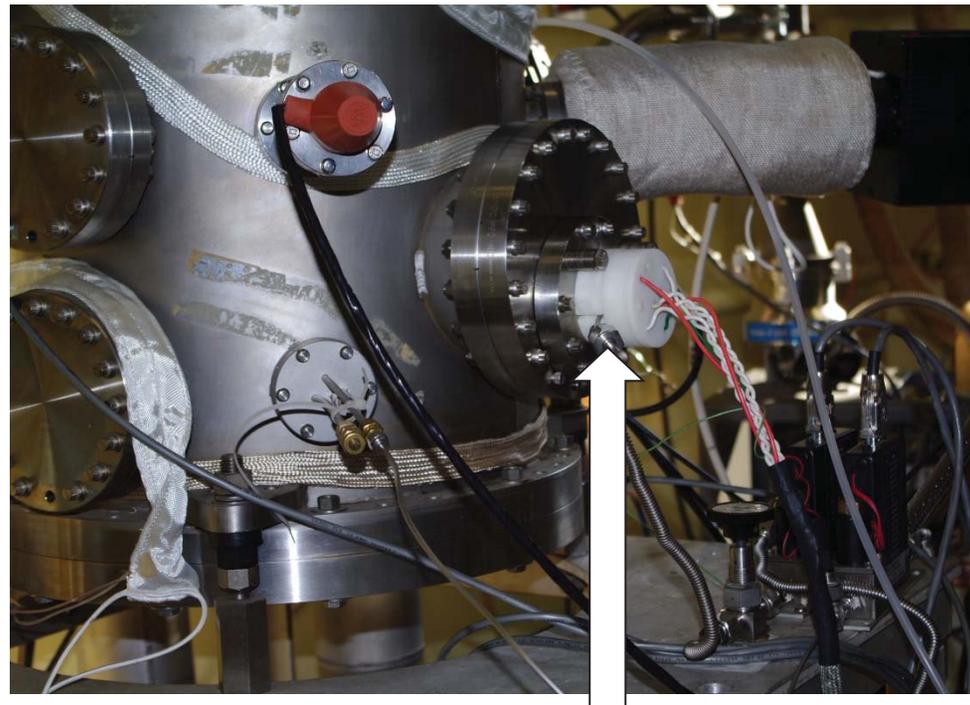


Spectral range: 190-2500 nm
Universal Reflectance Accessory

- Spectral range: 30-300 nm
- Source: Windowless H₂-purged source (H₂ emission lines between 90 nm and 160 nm and a continuum at higher
- Detector: PMT with fluorescence coating

Ion Beam Sputtering Coating Chamber

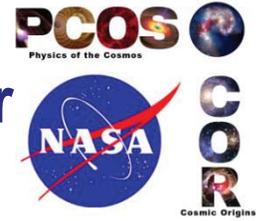
- Upgrade chamber with a two-gas flow controller system.
- Krypton gas to be used in the ion-beam sputtering depositions.
- Freon (CF_4) used as reactive gas to replenish the targets (MgF_2) stoichiometry.
- Added heaters to the chamber:
To improve microcrystalline film properties.



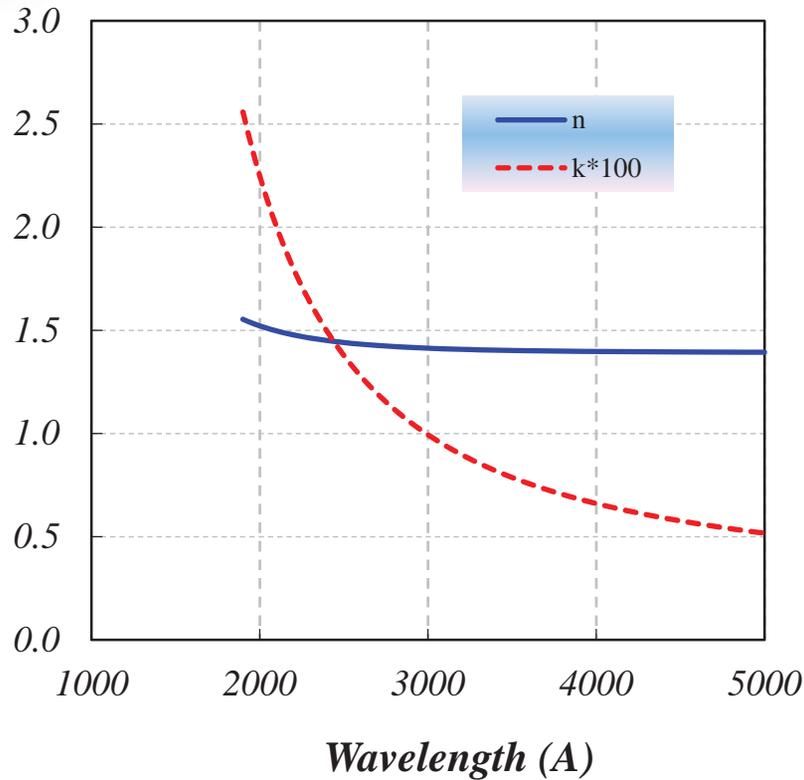
Reactive gas intake



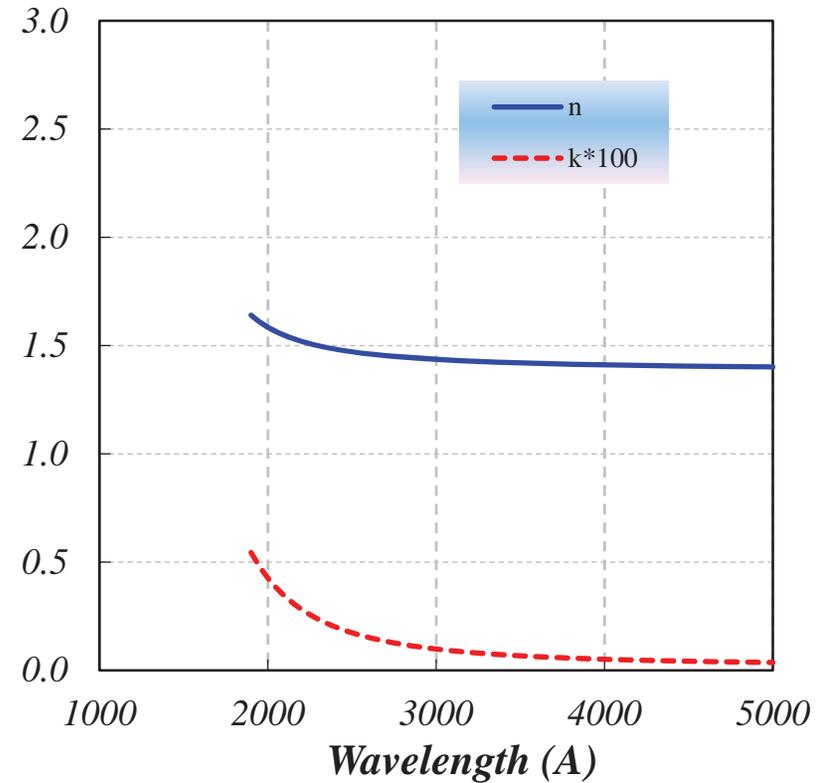
Comparison MgF2 Depositions in IBS Chamber



Normal IBS



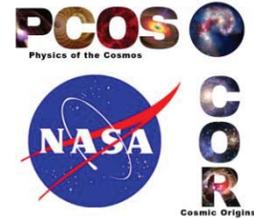
Reactive IBS



- Characterization of MgF2 films produced with the IBS process were not as good as conventional PVD results. As a result not coating runs of LiF films using reactive IBS were attempted
- Problem could be traced to at degradation of cathode filament due to reactive fluoride containing gas (Freon) in chamber
- Solution will be to procure an ion gun source without a filament:
 - Cost is over \$100k
 - Efforts were not pursued due to budget constraints



FUV Reflecting Dielectric



- Choose a high-index (H) and low-index (L) pair combination
- Form a pair of (H,L) layers with thicknesses equal to a Quarter-Wave Optical thickness at the design wavelength.
- Repeat the stack above until desired reflectance is achieved.



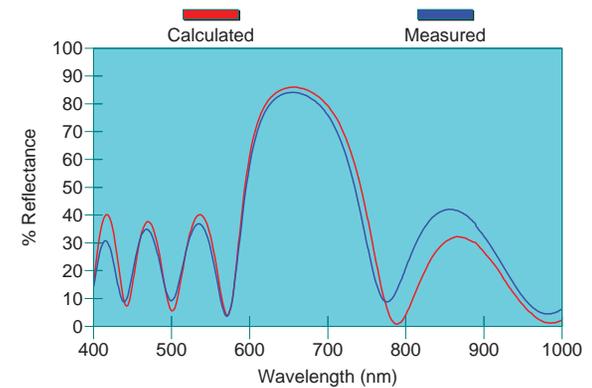
Note: The larger the difference between $(n_H - n_L)$ the better contrast and fewer layers needed to achieve a given R

Options for dielectric materials:

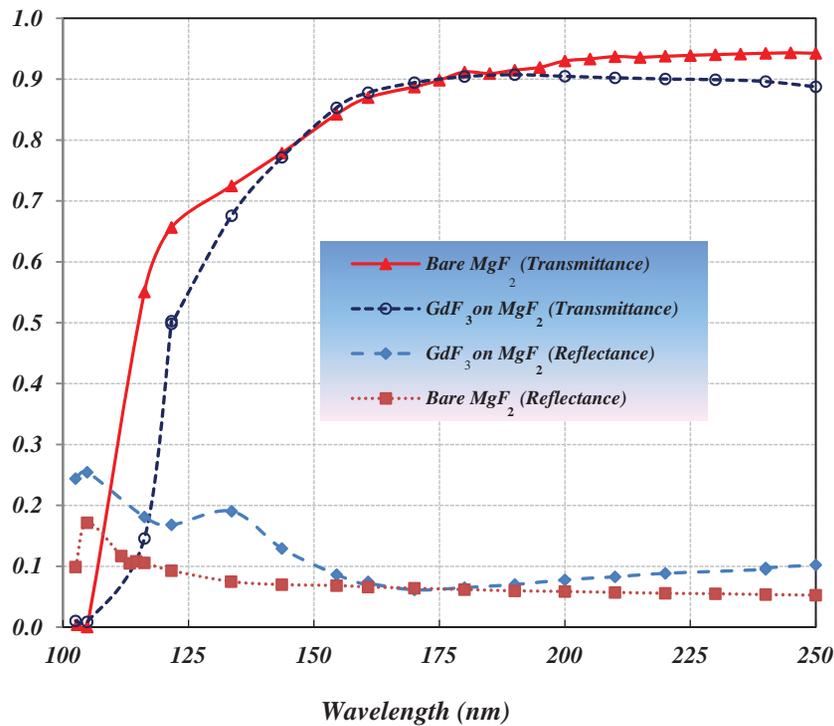
L: MgF_2 ($n \sim 1.45$)

H: GdF_3 ; LuF_3 ($n \sim ?$)

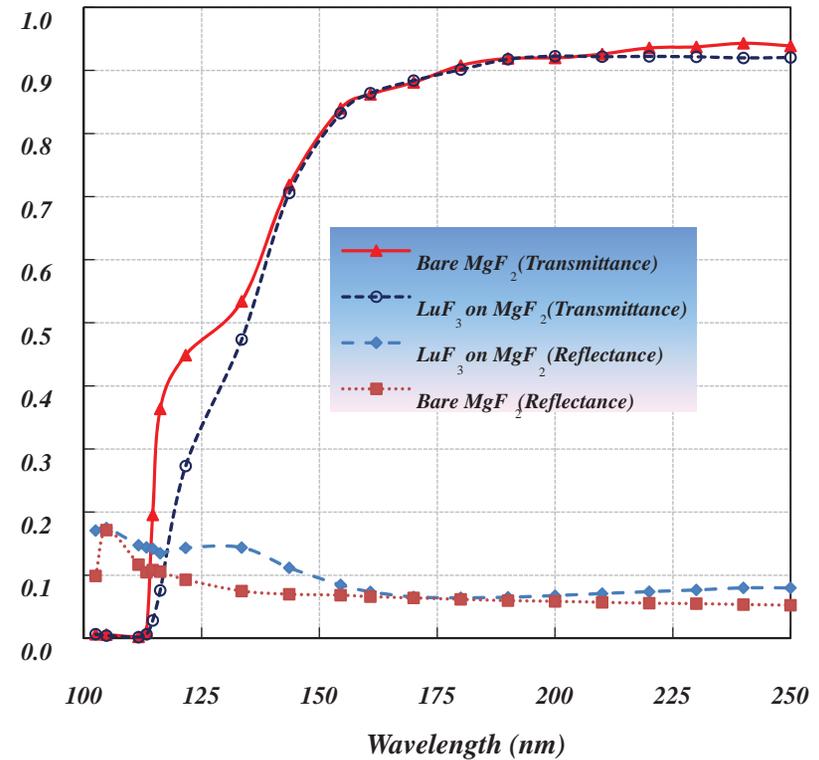
Modeled & Measured Result for Coating Run Trial #1



- 430 Å GdF₃ film on MgF₂ substrate

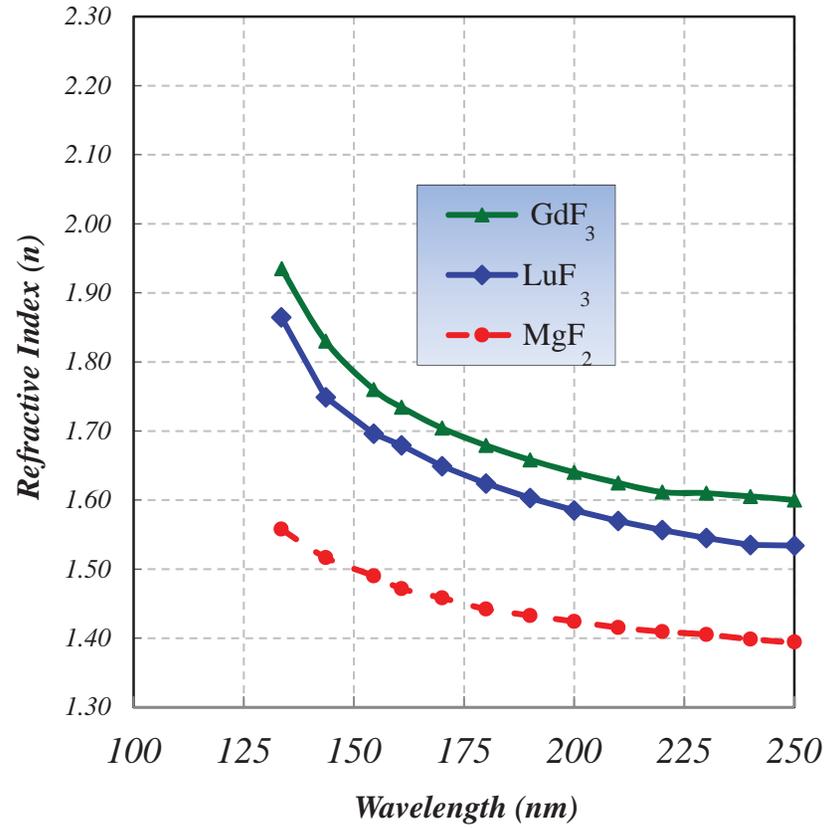
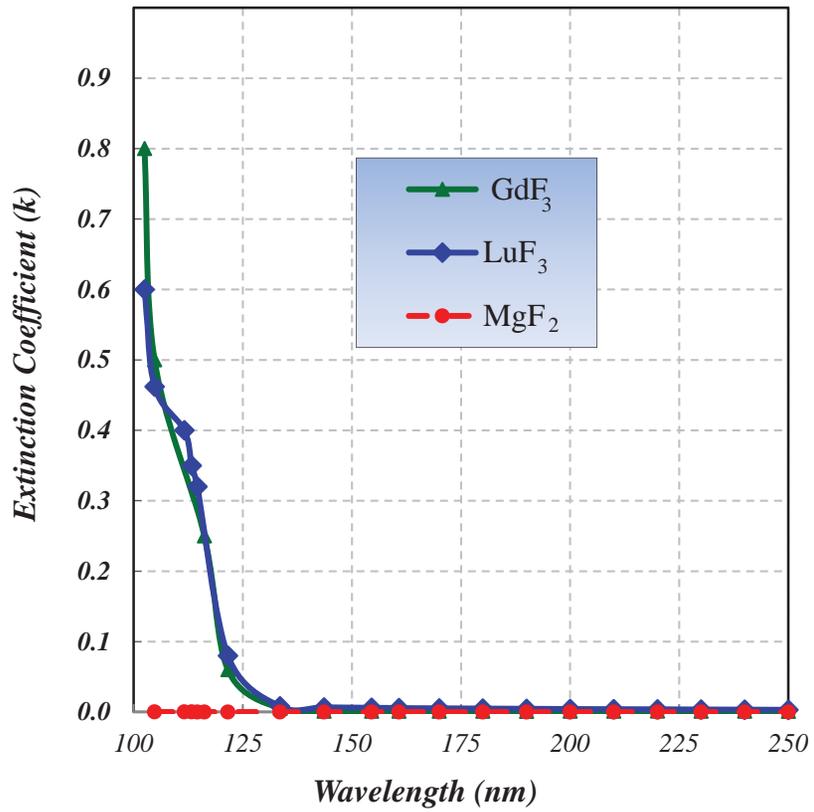


- 435 Å LuF₃ film on MgF₂ substrate

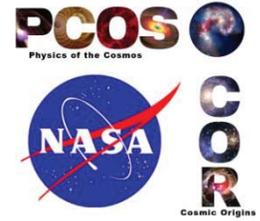




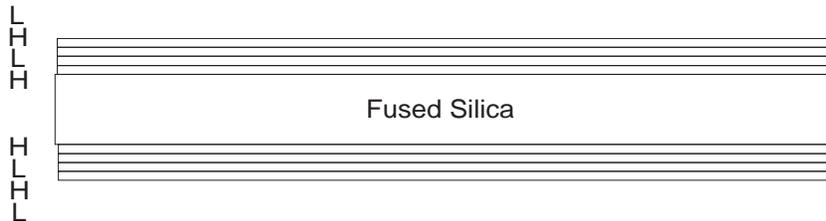
GdF₃ and LuF₃ Films Optical Constants



A/R Coating Example

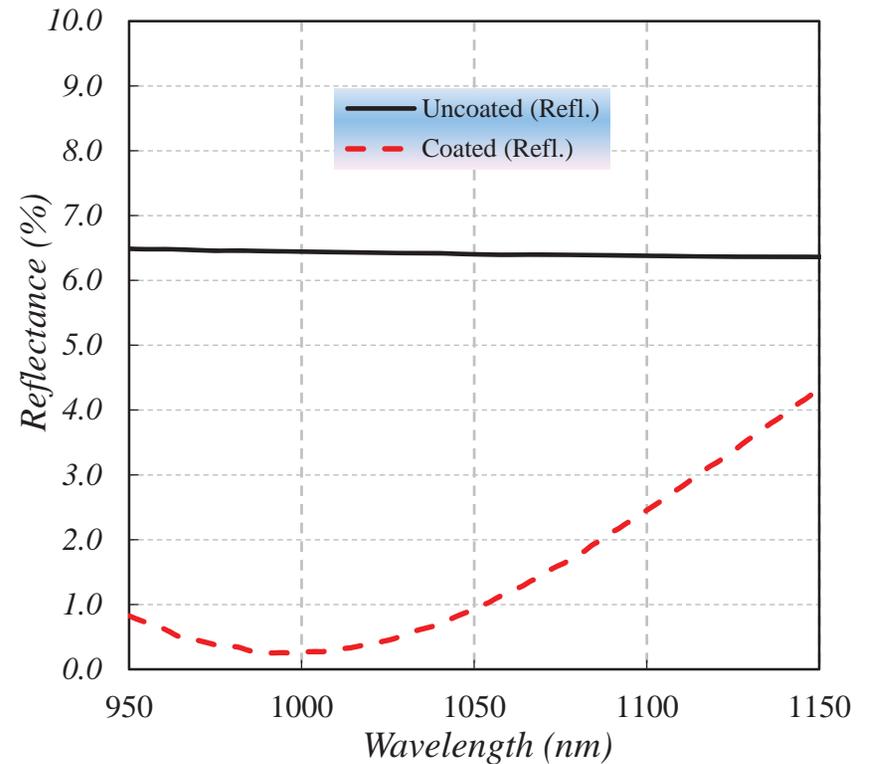


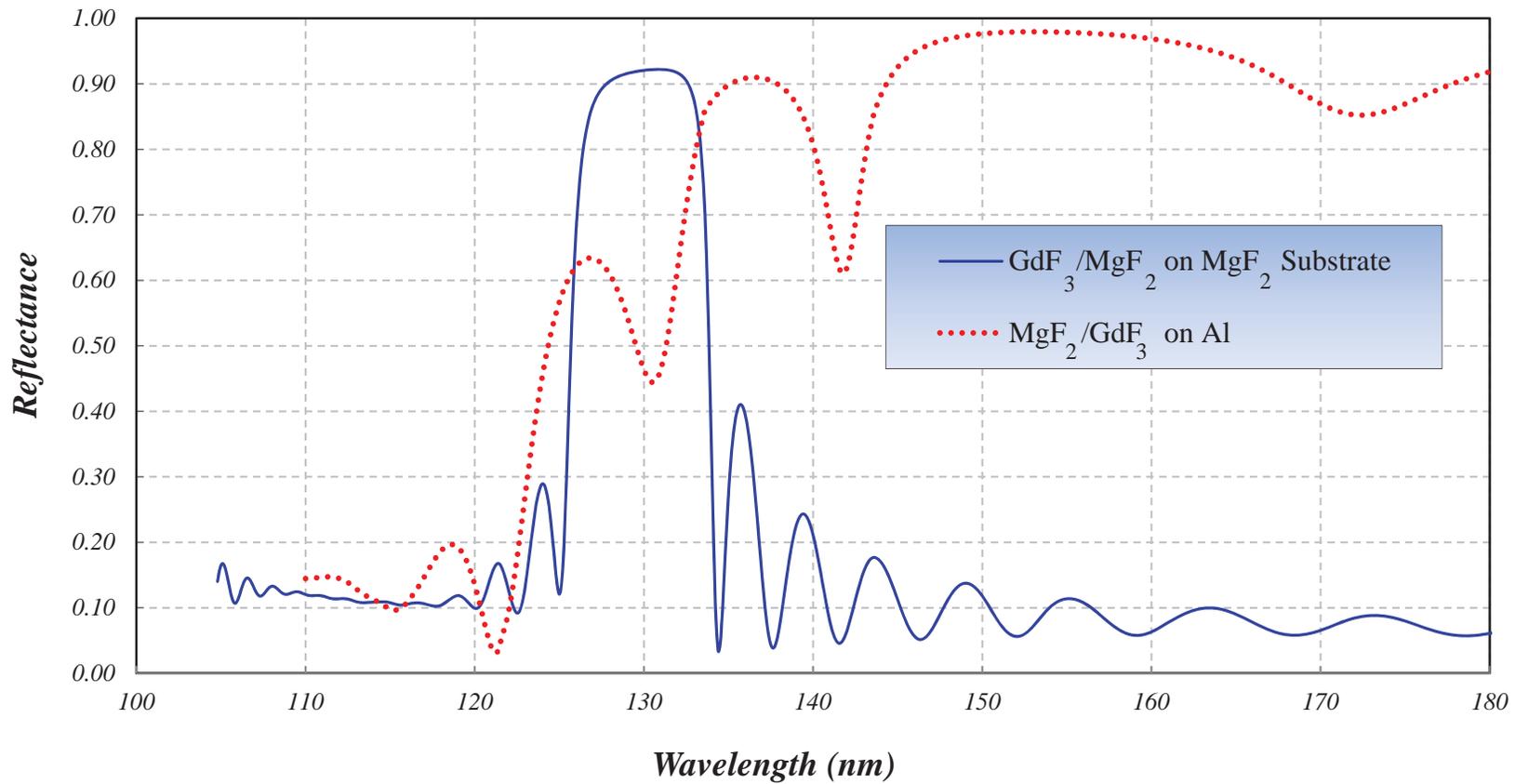
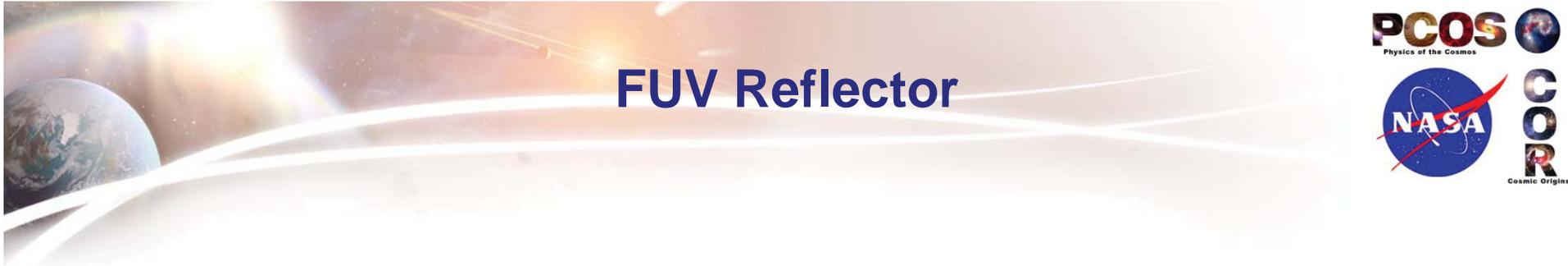
- A/R to suppress FS reflection losses near 1000 nm
- Design includes 2 layer pairs of $GdF_3(H)/MgF_2(L)$ (181 and 200 nm respectively) on both sides



Performance is 0.25% near 1000 nm

A/R Coating Performance

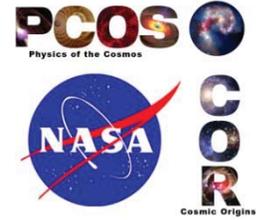




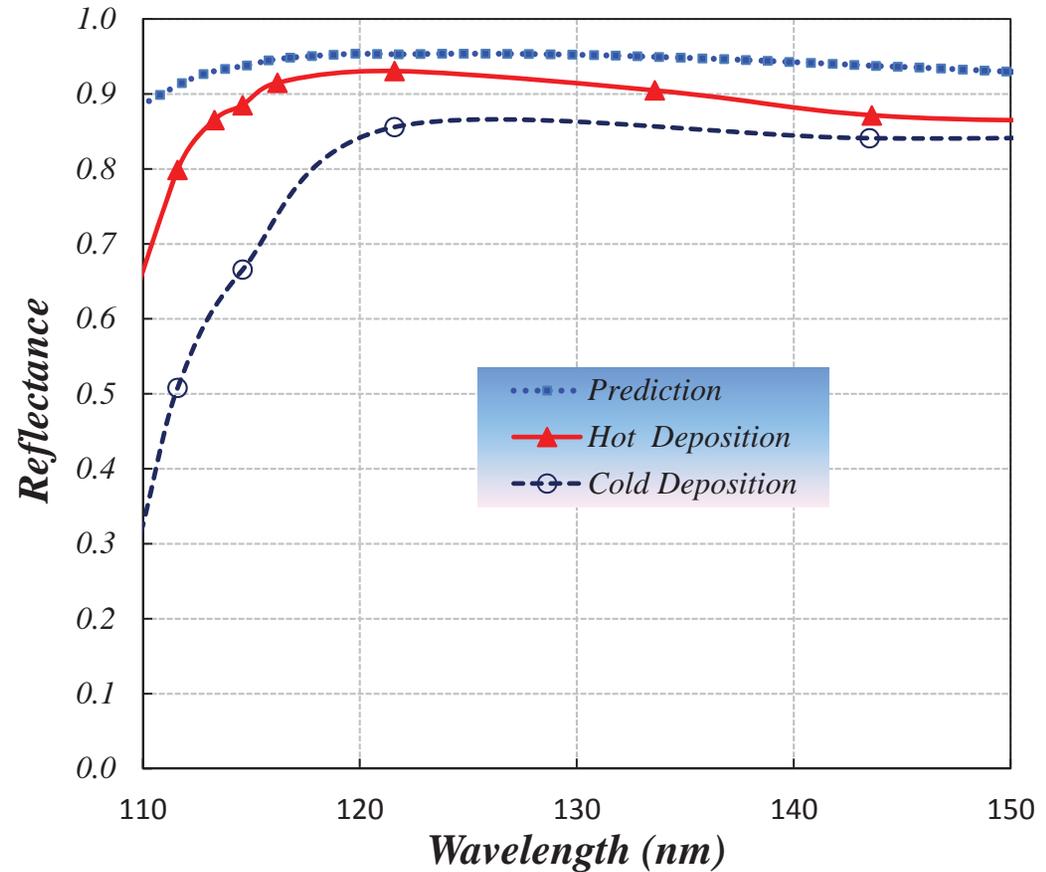
Design 1: 5 pairs MgF₂/GdF₃ on Al layer

Design 2: 10 pairs MgF₂/GdF₃ on MgF₂ substrate

Al+MgF₂ Mirror FUV Performance

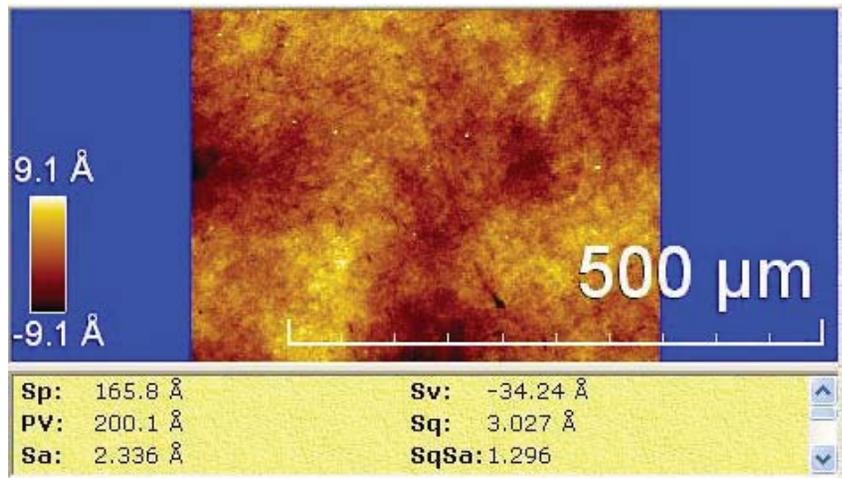


- Predicted vs. measured reflectance of bare Al and Al+MgF₂ reflectance (Al: 50.0 nm; MgF₂: 25.0nm)
- Enhanced performance is obtained by heating (~220 ° C) substrate during MgF₂ deposition
- Reflectance is > 80% even at 115.0 nm

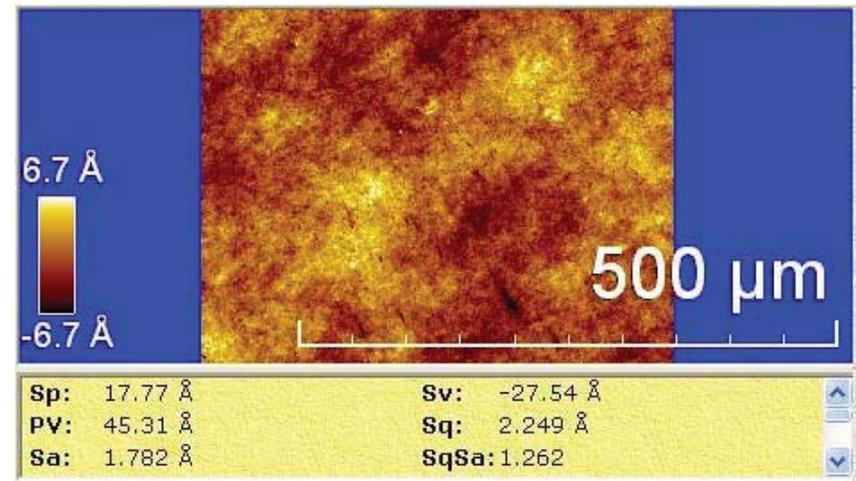


Micro-roughness Al+MgF2 Coatings

Standard Deposition



Hot Deposition

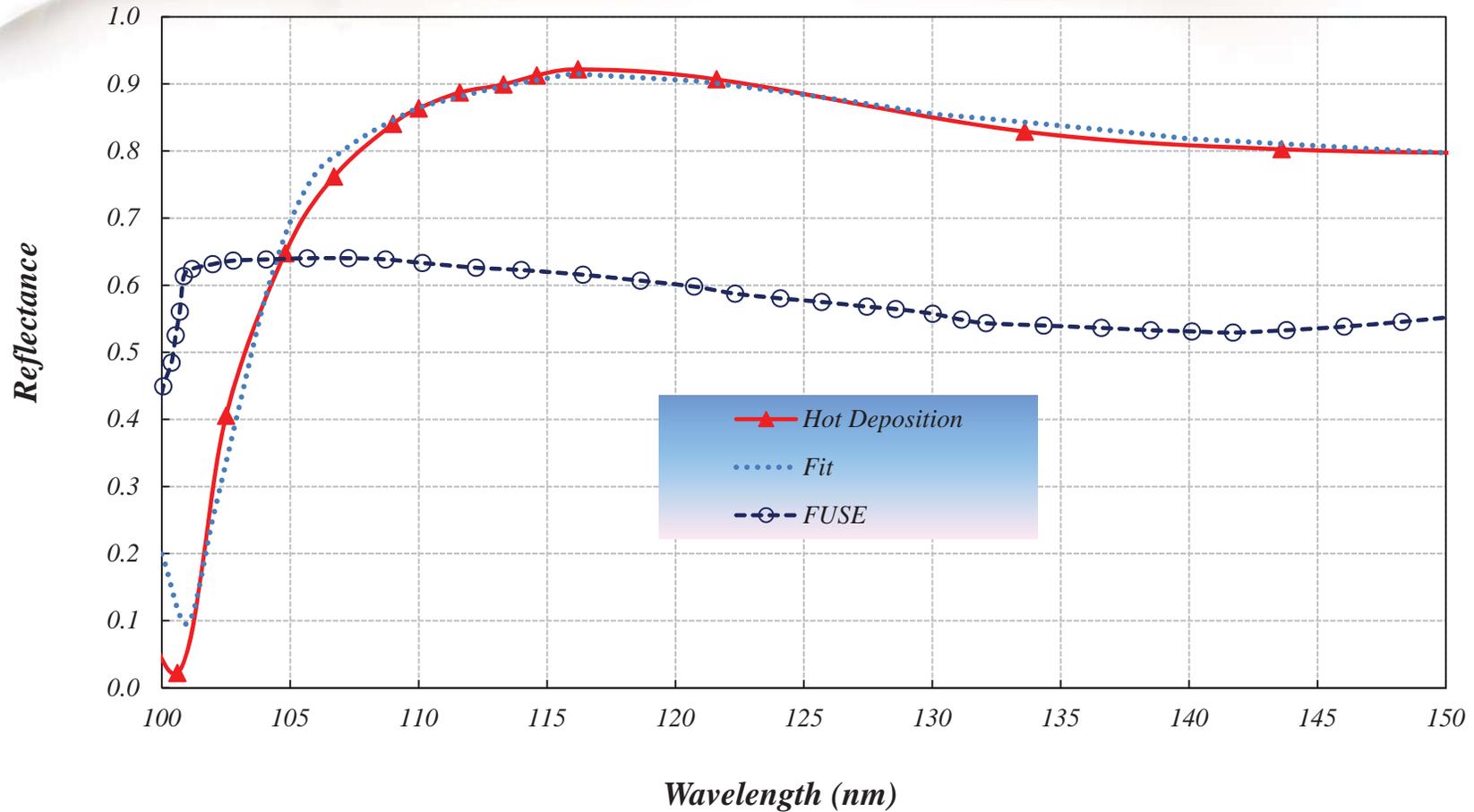
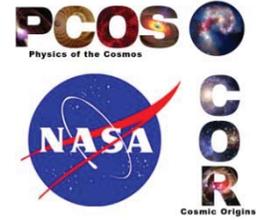


AM2 13 01C	x20 mag/ angstroms	PV (Å)	Sq (Å)
top left		75.58	6.146
top right		101.2	5.196
center		128	4.021
bottom left		200.1	3.027
bottom right		100	3.282
average		120.97	4.3344

AMCT 13 01A	x20 mag/ angstroms	PV (Å)	Sq (Å)
top left		45.31	2.249
top right		40.19	2.331
center		50.96	3.304
bottom left		44.39	2.923
bottom right		50.85	3.854
average		46.34	2.9322



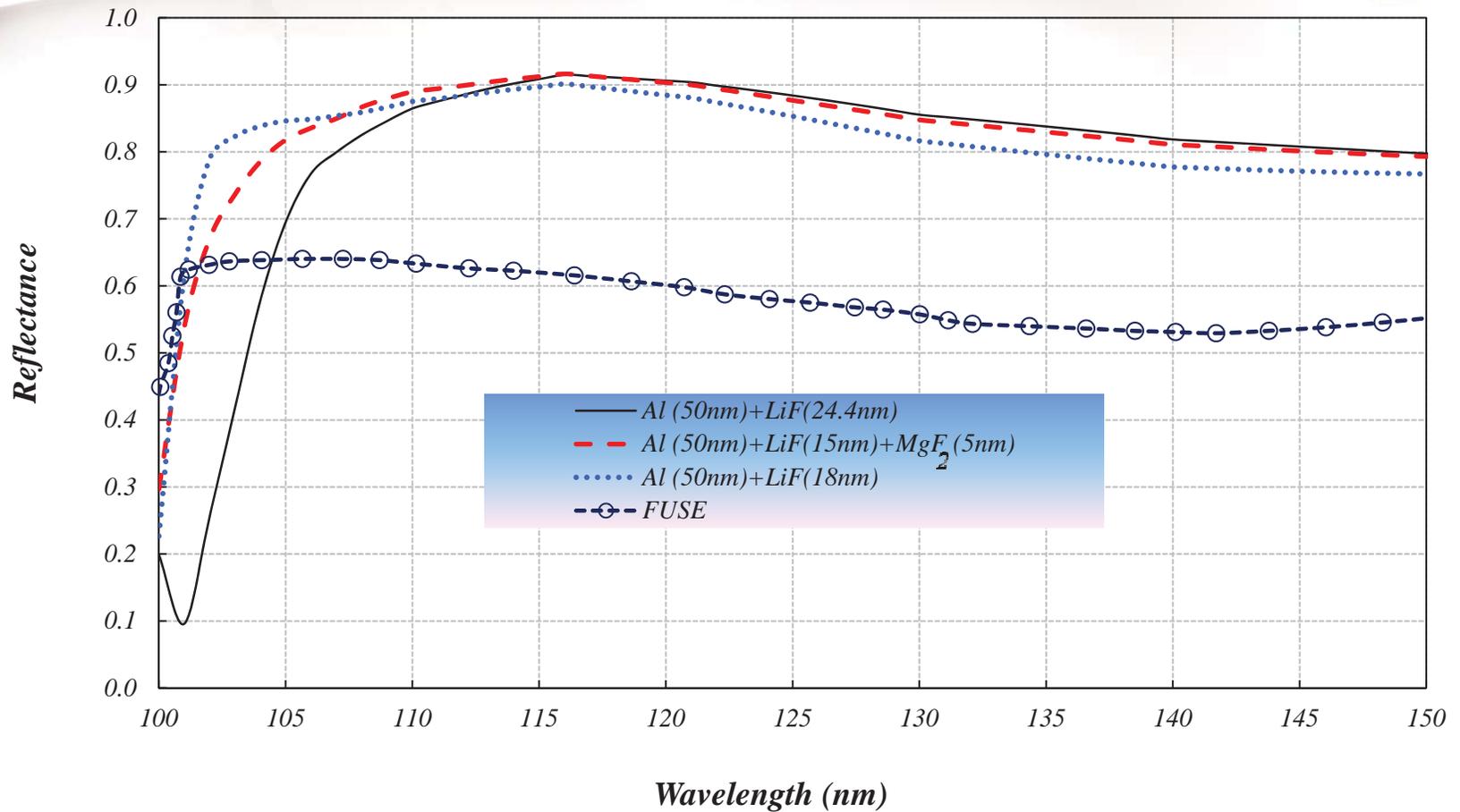
Al+LiF Mirror FUV Performance



Recipe: Al (43nm, ambient)+LiF(8nm, ambient)+LiF(16.4nm, 250° C)
 $R_{ave}(100-150nm)$: 59% (FUSE) 75% (Hot)



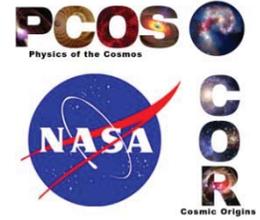
Al+LiF Mirror FUV Performance Cont..



Dual bowl fixture

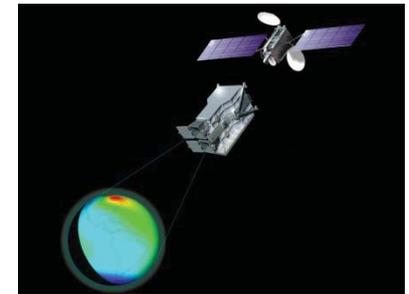
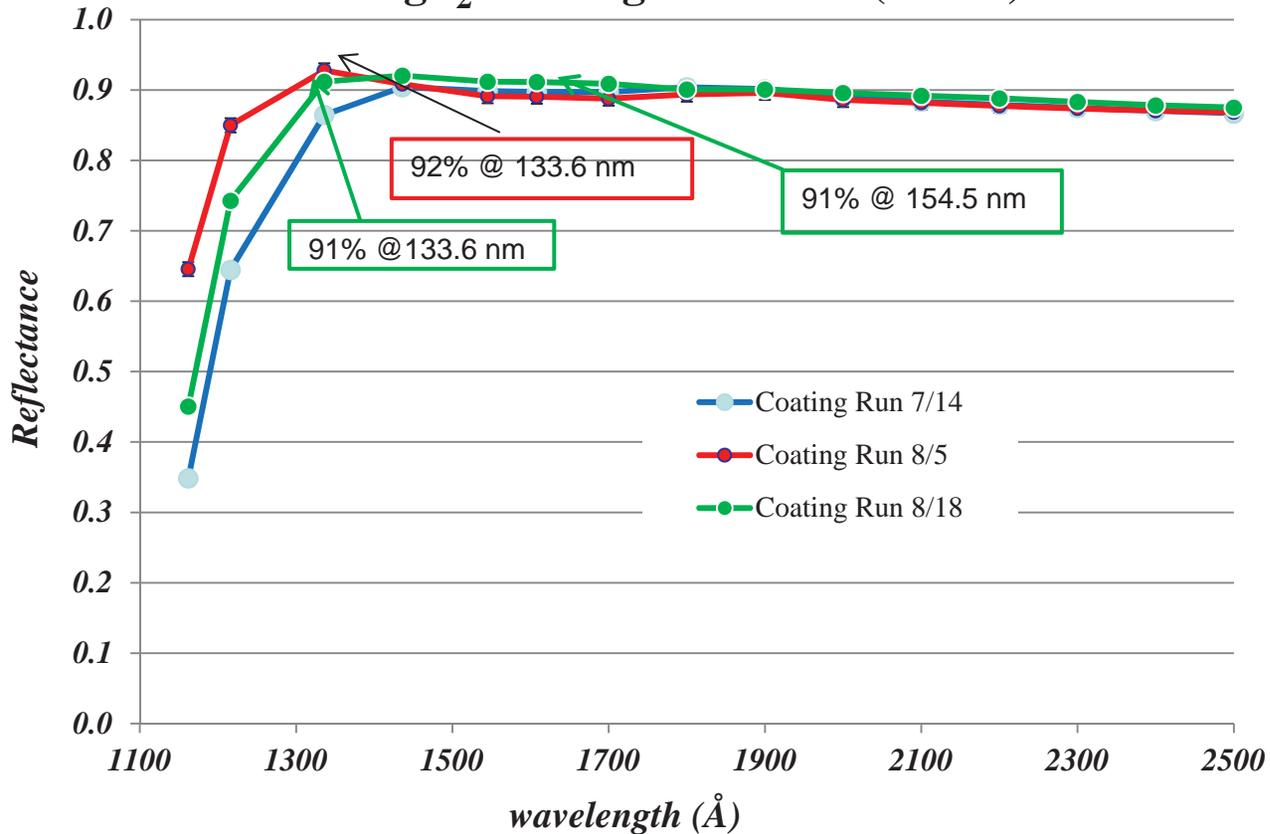


ICON/GOLD Coating Tasks

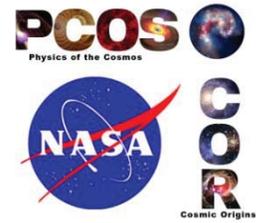


- ICON (Ionospheric Connection explorer): Study Earth's low-orbit ionosphere
- GOLD (Global-scale Observations of the Limb and Disk) : Imager to map Earth's thermosphere & ionosphere

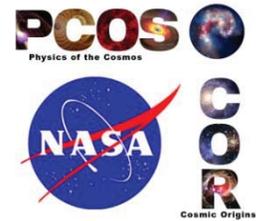
Al+MgF₂ Coating Test Runs (265°C)



Conclusions and Future Plans



- Reported gains in FUV reflectivity of Al+MgF₂ and Al+LiF mirrors by employing a 3-step process during PVD coating deposition of these materials.
- Successful demonstration of enhancement in FUV reflectance using a large 2-meter chamber.
- Characterization of lanthanide tri-fluoride material candidates to determine their FUV transparency for development of dielectric coatings.
- On-going task of depositing Al(50)+LiF(15nm)+MgF₂(5nm)
- Produce FUV reflector using dielectric (MgF₂/GdF₃) pairs
- GSFC Internal Research & Development to setup pilot program to study synthesis of MgF₂ films using ALD process



Acknowledgement

Collaborators: *Javier del Hoyo,*
 Steve Rice,
 Felix Threat,
 Jeffrey Kruk,
 Charles Bowers